

What is claimed is:

Sup 6 Q1
EM radiation
Y02 B6h
4.5.9

1. A method of detecting
electromagnetic and/or nuclear radiation,
comprising the steps of:
exposing a cantilever to a source of
5 radiation, the cantilever having at least one
physical property affected by radiation;
monitoring radiation-induced changes in the
at least one physical property; and
correlating changes in the at least one
10 physical property to a measure of radiation.

2. A method according to claim 1,
wherein the monitoring step includes monitoring
radiation-induced bending of the cantilever.

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3. A method according to claim 1,
wherein the monitoring step includes monitoring
radiation-induced changes in mechanical
resonance of the cantilever.

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same as cantilever
of claim 1*

4. A method according to claim 1,
further comprising forming a microcantilever
using a material or materials which heat when
exposed to radiation, changes in the at least
5 one physical property of the microcantilever
being temperature dependent, and the monitoring
step comprises monitoring temperature-dependent
changes in the at least one physical property of
the microcantilever.

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see above*

5. A method according to claim 1,
further comprising forming a microcantilever
using a material or materials which absorb
radiation and changes property as a function of
5 absorbed radiation, and the monitoring step
includes monitoring stress-induced changes in
the microcantilever and the correlating step
includes correlating changes in stress to the
presence of radiation.

6. A method according to claim 1,
wherein the microcantilever has an elastic
modulus which varies with exposure to radiation,
the at least one mechanical property of the
5 microcantilever varying with variations in the
elastic modulus.

7. A method according to claim ²⁵1,
further comprising the step of applying at least
one coating to the microcantilever made of a
material which interacts with radiation to vary
5 at least one physical property of the
microcantilever, the exposing step comprising
exposing the coated microcantilever to
radiation, and the correlating step includes
correlating changes in the at least one physical
10 property to the presence of the radiation.

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8. A method according to claim 1, further comprising the steps of directing a laser beam from a diode laser toward the cantilever, reflecting the laser beam from the cantilever, receiving the reflected laser beam at a position sensitive detector which generates a PSD signal, and detecting radiation based on the PSD signal.

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9. A method according to claim 1, further comprising coating the cantilever with or fabricating the cantilever from a piezoresistive material which has a resistivity which varies with bending of the microcantilever, and the correlating step comprises correlating changes in resistivity of the piezoresistive material to the presence of radiation.

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10. A method according to claim 1, further comprising placing the microcantilever in a capacitor having a capacitance which varies with movement of the microcantilever, and the correlating step includes correlating changes in capacitance to the presence of radiation.

11. A method according to claim 2,²⁵
further comprising forming an array of
microcantilevers and the exposing step includes
5 exposing the array of microcantilevers to
radiation.

12. A method according to claim 1,²⁵
further comprising coating the microcantilever
with a material which produces a bimetallic
effect and thus bending of the microcantilever
5 when heated, the exposing step comprises
exposing the microcantilever to a radiation
which induces heating and thus bending of the
microcantilever, and the correlating step
comprises correlating bending of the
10 microcantilever to the presence of radiation.

13. A method according to claim 1,²⁵
further comprising oscillating the
microcantilever, determining the microcantilever
resonance properties, and detecting radiation
5 based on changes in the resonance response.

14. A method according to claim 1,
further comprising mechanically oscillating the
microcantilever using a piezoelectric device
attached to the microcantilever, determining the
microcantilever resonance properties, and
detecting radiation based on changes in the
resonance response.

15. A method according to claim 1,
further comprising mechanically oscillating the
microcantilever using electrical stimulation to
a piezoresistive coating attached to the
microcantilever, determining the microcantilever
resonance properties, and detecting radiation
based on changes in the resonance response.

16. A method according to claim 1,

further comprising placing the microcantilever within an oscillatory tank circuit, wherein the cantilever is disposed between poles of a capacitor or constitutes one pole of a capacitor, mechanically oscillating the microcantilever using electrostatic forces generated within the capacitor, determining the microcantilever resonance properties, and detecting radiation based on change in the resonance response.

17. An apparatus for detecting electromagnetic and nuclear radiation, comprising the steps of:

5 a radiation sensor having an element exposed to a source of radiation, the sensor having at least one physical property affected by radiation;

10 means for monitoring radiation-induced changes in the at least one physical property of the sensor; and

means for correlating changes in the at least one physical property to a measure of radiation.

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18. An apparatus according to claim 17, wherein the sensor comprises a microcantilever connected to a base, where the microcantilever consists of a material or layered materials which converts energy of radiation, if present, into a physical change in the microcantilever.

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19. An apparatus according to claim 18, wherein the microcantilever is comprised of at least one coating, where the at least one coating includes a first metallic coating which, together with the microcantilever, exhibits a bimetallic effect when exposed to energy of radiation.

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20. An apparatus according to claim 19, wherein the first metallic coating covers a portion of one surface of the microcantilever and is separated from the base by a space.

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21. An apparatus according to claim 19, wherein the first metallic coating covers a portion of one surface of the microcantilever and

is separated from the base by an insulator.

22. An apparatus according to claim 18, further comprising a second coating on the microcantilever, consisting of a radiation absorbing material that increases the radiation flux absorbed by the microcantilever.

23. An apparatus according to claim 18, wherein the microcantilever or layered material on the microcantilever exhibits a change in chemical or physical properties upon absorption of radiation.

24. An apparatus according to claim 18, wherein the microcantilever or layered material on the microcantilever exhibits a change in elastic modulus upon radiation damage induced by absorption of nuclear radiation.

Q6
no 1st coating
in patent drawing
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25. An apparatus according to claim 17, further comprising a reference sensor of substantially similar construction and local environment and located in proximity to the radiation sensor, but not exposed to radiation, whereby a differential response between the reference sensor and the radiation sensor provides a calibration that reduces extraneous environmental factors common to both assemblies.

26. A sensor for detecting radiation, comprising:

a cantilever substrate coupled to a base; and

a metal film bonded in confronting relationship to the cantilever substrate.

27. A sensor according to claim 26, further comprising:

a thermally-absorptive film in confronting relationship with the metal film for increasing the radiation flux absorbed by the metal film.

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28. A sensor according to claim 26,
wherein the cantilever substrate is coated with
a piezoresistive material.

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29. A sensor according to claim 26,
further comprising a stress-sensitive coating
bonded in confronting relationship to the
cantilever substrate.

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30. A sensor according to claim 26,
wherein the cantilever substrate is made of a
semiconductor material selected from the group
consisting of silicon and silicon nitride.

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31. A sensor according to claim 26,
wherein the sensor assembly is disposed in an
array of substantially similar sensor
assemblies. C

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